

ABSTRACT

There is included (a) forming a first film having a predetermined composition on a first substrate by supplying a first processing gas to the first substrate; and (b) forming a second film having a composition different from the composition of the first film on the first substrate or a second substrate by performing a cycle including a supply of a second processing gas to the first substrate or the second substrate, wherein when performing (b) in a second state in which the second film adheres to an outermost surface of a member in the process container, the cycle is performed a predetermined m times, and wherein when performing (b) in a first state in which the first film adheres to the outermost surface, the cycle is performed $m^{\pm}$ times, or the cycle is performed the m times after performing a precoating process of forming the second film.

FIG. 6